

# Trichlorosilane A Key Material in The Semiconductor Industry Application Usage Sihcl3

## **Basic Information**

Place of Origin: China
Brand Name: CMC
Certification: COA
Model Number: Sihcl3
Minimum Order Quantity: 1kg

Price: US \$500/kg
Packaging Details: Cylinder/Tank
Delivery Time: 30 days
Payment Terms: L/C, T/T

• Supply Ability: 2000 Tons/Year



## **Product Specification**

• Product Name: Trichlorosilane

• Purity: 99.99%

• Grade: Electron Grade

By Sea • Transport: · Model No: Sihcl3 • Transport Package: Tanker Specification: Y-Cylinder CMC Trademark: • Origin: China . HS Code: 2812190091 • Supply Ability: 500ton/Month • CAS No.: 10025-78-2 • Formula: Sihcl3 • EINECS: 7783-82-6 Industrial Pure Air . Constituent:



## **Product Description**

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Trichlorosilane (SiHCl3) is a chemical compound composed of one silicon atom bonded to three chlorine atoms and one hydrogen atom. It is a colorless, volatile liquid at room temperature. Here are some key points about trichlorosilane:

Chemical Composition: Trichlorosilane consists of one silicon (Si) atom bonded to three chlorine (Cl) atoms and one hydrogen (H) atom. Its chemical formula is SiHCl3.

Properties: Trichlorosilane is a volatile liquid that boils at around 31.8 degrees Celsius (89.2 degrees Fahrenheit) and has a melting point of -122 degrees Celsius (-187.6 degrees Fahrenheit). It is highly reactive and flammable. Trichlorosilane readily decomposes in the presence of moisture or water, releasing hydrogen gas and forming silicic acid.

Production: Trichlorosilane is primarily produced through the reaction of metallurgical-grade silicon (usually in the form of chunks or powder) with hydrogen chloride (HCl) gas at high temperatures:

Si + 3HCl → SiHCl3 + H2

This reaction typically occurs in the presence of a catalyst and is conducted in a closed system.

Uses: Trichlorosilane has various industrial applications:

Silicon Production: It is a key intermediate in the production of high-purity silicon. Trichlorosilane is used as a precursor in the Siemens process or the modified Siemens process, which involves the production of polycrystalline silicon for use in semiconductors and solar cells.

Chemical Synthesis: Trichlorosilane is used as a source of silicon in the synthesis of various silicon compounds, including silicones, silanes, and silicon carbide

Hydrogen Production: Trichlorosilane can be used as a source of hydrogen gas through its reaction with water vapor or steam:

SiHCl3 + 3H2O → SiO2 + 3H2 + 3HCl

This reaction generates hydrogen gas for various industrial applications.

Metal Surface Treatment: Trichlorosilane is used as a surface treatment agent for metals to improve adhesion or provide a protective coating. Safety Considerations: Trichlorosilane is a flammable liquid and should be handled with caution. It reacts vigorously with water, releasing hydrogen gas and forming corrosive silicic acid. Trichlorosilane vapors are also toxic and can cause respiratory irritation. Proper safety precautions, such as appropriate ventilation, protective equipment, and safe handling procedures, should be followed when working with trichlorosilane. It's important to handle trichlorosilane safely and follow proper protocols to minimize risks associated with its reactivity, flammability, and

#### Basic Info.

potential health hazards.

Model No:	SiHCl3	Quality	Electron Grade
Transport Package	Y-Cylinder, T-Drum, Tt, Tanker	Specification	20L, 40L, 280L and customizable
Trademark	CMC	Origin	Suzhou, China
HS Code	2812190091	Production Capacity	500ton/Month

### Specification:

**Trichlorosilane** is a silicon precursor for epitaxial silicon-containing thin films, especially for the preparation of starting wafers.

Purity %:	≥99.85	
Resistivity:	≥ 300 ohm-cm	
Boron:	≤ 0.1 ppba silicon	
Total Carbon:	≤ 5 ppma	
Iron:	≤ 5 ppba	
Other Chlorosilane:	≤ 500 ppm	
Cylinder State @ 21.1°C:	Liquid	
Flammable Limits In Air :	7-83%	
Auto Ignition Temperature (°C):	182	
Molecular Weight (g/mol):	135.45	
Specific gravity (air =1):	4.67	
Critical Temperature ( °C ):	242.5	

### **Detailed Photo**



Company

Profile



Shanghai Kemike Chemical Co., Ltd is staffed by trained personnel, combine many years experience in Gas industry. We supply cylinder gas, electronic gas, etc., and the gas holder, panel, valves and fittings and other equipment, parts and engineering services to our customers in China and worldwide; The products are involved in various industrial fields, such as semiconductor chip, solar cell, LED, TFT-LCD, optical fiber, glass, laser, medicine, etc., Our mission is to partner with our global customers to provide support, solutions and quality products that are innovative, reliable, and safe.

Our products mainly include: H2, O2, N2, Ar, CO2, propane, acetylene, helium, laser mixed gas, SiH4, Sih2cl2, SiHCL3, SiCL4, NH3, CF4, NF3, SF6, HCL, N2O, doping mixed gas (TMB, PH3, B2H6) and other electronic gases.

CH3F F6+CI2 WF6 SiCI4 NH3 NH3 SiH4 Kr H<sub>2</sub>S

C2 C3F8 C3F8 **TEOS** CH4 PH<sub>3</sub> SF6 HCI+Ne 4MS

SiH2 CF4 C4F8

SiF4 **C3H8** CI2

DCE BBr3 **C3H6** 

POCI3 SO2 N2

BCI3 D2 CO<sub>2</sub>

SiHCI3 CH2F2 HF

**TMAI** DMZn DEZn AsH3

GeH4

C2H4

C2H6

**B2H6** 

C2H2

H2Se

HBr

GeCl4

COS

Xe+NO

TMB+H2

He +As

Ge+Se

D+B

CO+NO

Ar+O2





